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(54) ABSORBING ARTICLE CONTAINING POLYETHER-CONTAINING HOT MELT ADHESIVE AND HOT MELT ADHESIVE COMPOSITION CONTAINING SURFACTANT IN COMBINATION WITH POLYETHER

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain an absorbing article improved in the capacity of suction by mixing a base polymer in an amount effective to render a hot melt composition adhesive with a polyether in an amount effective to form a specified contact angle between an article and the fluid to be to come into contact with the article and to lower the surface tension of the fluid.

SOLUTION: The polyether comprises at least one polyether essentially consisting of homogeneous, alternating or random units having -R-O- (wherein R is a 2C or higher alkyl) and used in an amount effective for forming a contact angle between an article and the fluid to be to come into contact with the article of below about 90 degrees and to show a decrease in surface tension of about 40 dyn/cm. When the polyether is incorporated in a hot melt adhesive composition, the repeated penetration time of the article can be improved. Further, when the polyether is combined with an effective amount of at least one surfactant, the repeated penetration time and the fluid suction capacity can be improved.

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